Plasma & Sputtering Sources

Rectangular Magnetrons

IONIX® rectangular magnetron sputtering sources with advanced water cooling circuits are designed for industrial production purposes, offering:

- High-reate metallic sputtering
- RF sputtering of dielectric targets
- Pulsed reactive mode sputtering for high rate
- Deposition of dielectric thin films

Advanced water cooling

Directed cooling water flow and multipolar magnet arrays accomodate the use of clamped targets at power levels of 20W/cm2 (Cr, Al) and above.

Rectangular Magnetrons				
Target width "A"	**Target length "B"**	**Cathode width "C"**	**Cathode length "D"**	**Height "H"**
63 mm / 2,5"	300 ... 1000 mm	102 mm	„B" + 40 mm	64 mm
89 mm / 3,5"	300 ... 1000 mm	135 mm	„B" + 47 mm	75 mm
100 mm / 4"	300 ... 1000 mm	147 mm	„B" + 47 mm	66 mm
127 mm / 5"	300 ... 2000 mm	172 mm	„B" + 47 mm	71 mm
152 mm / 6"	300 ... 2000 mm	205 mm	„B" + 57 mm	80 mm
200 mm / 8"	300 ... 3000 mm	265 mm	„B" + 75 mm	84 mm

Magnet Array Options

1. Standard magnet arrays

- Extended film homogeneity
- High rates
- Target utilization 30 - 35 %
- Stable operation in AC and RF mode

2. Multi-polar magnet arrays

- Target utilization 35 - 45 %

3. Coil assisted magnet arrays

- To unbalance
- Adjust target utilization

4. Low pressure magnet arrays

- p = 7 x 10-4 mbar and below